

Supporting Information

Efficient oxidative hydrogen peroxide production and accumulation in photoelectrochemical water splitting using a tungsten trioxide/bismuth vanadate photoanode

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Experimental Section

All reagents were commercially available, of reagent grade, and used without further purification.

Preparation of the WO₃/BiVO₄ photoelectrodes

The WO₃/BiVO₄ photoelectrode was prepared on F-doped SnO₂ conductive glass (FTO) substrate (Nippon Sheet Glass Co., Ltd.) by spin coating. Typically, *N,N*-dimethylformamide (DMF) solutions of tungsten hexachloride (WCl₆) adjusted to 504 mM was coated on FTO by spin coating (1000 rpm, 15 s), and then, the film was calcined at 500°C for 30 min. The coating of WO₃ layers was again performed using WCl₆ adjusted to 252 mM, resulting in the formation of a WO₃ underlayer possessing a rough porous surface.

The mixed solution (Bi:V=1:1) of bismuth oxide and vanadium oxide of EMOD (enhanced metal organic decomposition) materials (Symetrix Co., USA) solved in butyl acetate containing ethylcellulose as a thickener and aggregation inhibition agent was coated on the WO₃ underlayer by spin coating (500 rpm, 15 s). Then, the film was calcined at 550°C for 30 min to form WO₃/BiVO₄ photoelectrodes.

Characterization

The WO₃/BiVO₄ photoanodes were characterized using X-ray photoelectron spectrometer (XPS, Ulvac-Phi, XPS-1800), X-ray fluorescence spectroscopy (XRF, Rigaku, ZSXmini), scanning electron microscopy (SEM, Hitachi, Ltd., S-4800) and scanning transmission electron microscopy (STEM, Hitachi High-Technologies Co., Ltd., HD-2700).

Photoelectrochemical production of H₂O₂ and H₂

1. Photoelectrochemical properties

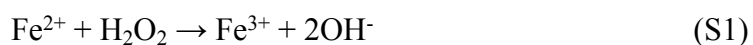
The photoelectrochemical performance of the WO₃/BiVO₄ photoelectrodes was measured using an electrochemical analyzer (BAS. Inc., ALS660B) and a solar simulator (SAN-EI ELECTRIC Co., XES-151S), calibrated to AM-1.5 (1 SUN, 100 mW cm⁻²) using a spectroradiometer (SOMA Optics, Ltd.). The irradiation area (0.28 cm²) was limited using a black mask. The simulated solar light was irradiated from the semiconductor side.

The current-voltage (*I-V*) characteristics were studied using a one-compartment cell consisting of a WO₃/BiVO₄ photoelectrode equipped with a back reflection plate as the working electrode, a Ag/AgCl electrode as the reference electrode, and a Pt mesh as the counter electrode at a low scan rate (50 mV s⁻¹). Aqueous solution of 0.5 M KHCO₃ adjusted to pH 7.3 by CO₂ gas bubbling, 0.5 M K₂SO₄ (pH 6.2), 0.5 M H₃BO₃ adjusted to pH 7.1 by the addition of KOH, and 0.5 M phosphate buffer (pH 6.9) were utilized as electrolytes.

2. Production and/or accumulation of H₂O₂ and H₂ using a two-compartment cell

The production and accumulation of H₂O₂ and H₂ were performed with CO₂ or Ar gas bubbling using a two-compartment cell equipped with a Nafion membrane (thickness 0.0035 in.) as an ion-exchange membrane between the anode and cathode. Aqueous solution (anode: 35 mL, cathode: 35 mL) of 0.1–2.0 M KHCO₃ (pH 6.9–7.7), 0.5 M K₂SO₄ (pH 6.2), 0.5 M H₃BO₃+KOH (pH 7.1), and 0.5 M phosphate buffer (pH 6.9) were utilized as electrolytes. In the photoelectrochemical production and accumulation of H₂O₂ and H₂ using a two-compartment cell, anode electrodes possessing size of 1.2 cm×5.5 cm were used without a black mask.

The amount of H₂O₂ in the liquid phase of the anode was measured by colorimetry of the color changes from Fe²⁺ to Fe³⁺, as shown in Equation (S1)¹, using a microplate reader (Tecan Japan Co., Ltd., infinite M200PRO).



In aqueous solution of 0.1–0.5 M KHCO₃, 0.5 M K₂SO₄, 0.5 M H₃BO₃+KOH, and 0.5 M phosphate buffer, 0.1 mL of 0.1 M FeCl₂ in 1.0 M HCl aqueous solution was added to a mixed solution containing 1.0 mL of sample and 0.9 mL of 1.0 M HCl aqueous solution. Then, the H₂O₂ concentration was measured by Fe³⁺ colorimetry (330 nm). In 1.0–2.0 M KHCO₃ aqueous solution, 0.1 mL of 0.1 M FeCl₂ in 1.0 M HCl was added to a mixed solution containing 1.0 mL of sample and 0.9 mL of 3.0 M HCl aqueous solution. Then, the H₂O₂ concentration was measured by Fe³⁺ colorimetry (330 nm). The amounts of O₂ in the gas phase of the anode and H₂ in the cathode were measured using a Shimadzu GC-8A gas chromatograph equipped with a MS-5A column.

The Faraday efficiencies of H₂ and H₂O₂ ($\eta(\text{H}_2)$ and $\eta(\text{H}_2\text{O}_2)$) can be calculated as shown in Equation (S2), which takes into consideration the reaction shown in Equation (2-3).

$$\begin{aligned}
&\eta(\text{H}_2) \text{ or } \eta(\text{H}_2\text{O}_2) \\
&= [\text{amount of generated H}_2 \text{ or H}_2\text{O}_2] \times 100 \\
&\quad / [\text{theoretical amount of H}_2 \text{ or H}_2\text{O}_2] \\
&= [\text{amount of generated H}_2 \text{ or H}_2\text{O}_2] \times 100 \\
&\quad / [\text{amount of generated electrons} / 2] \qquad \qquad \qquad (\text{S2})
\end{aligned}$$

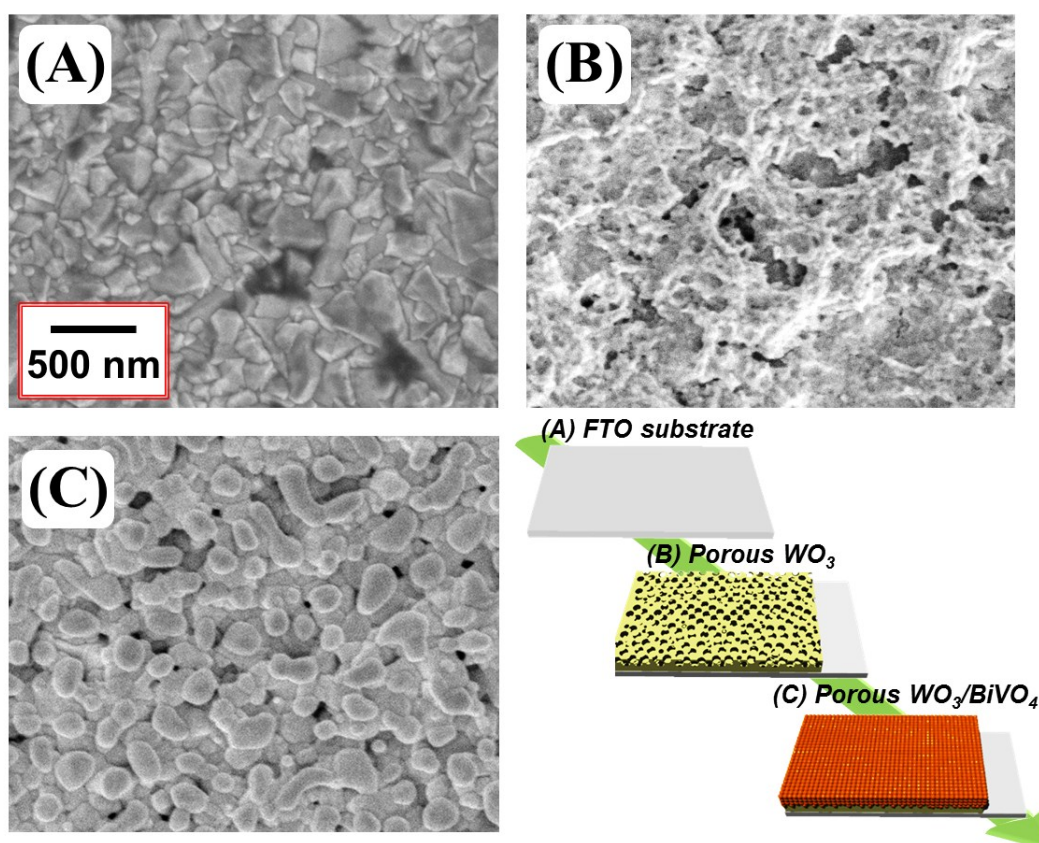


Fig. S1 SEM images of (A) FTO substrate, (B) WO_3 underlayer, and (C) $\text{WO}_3/\text{BiVO}_4$ photoelectrode.

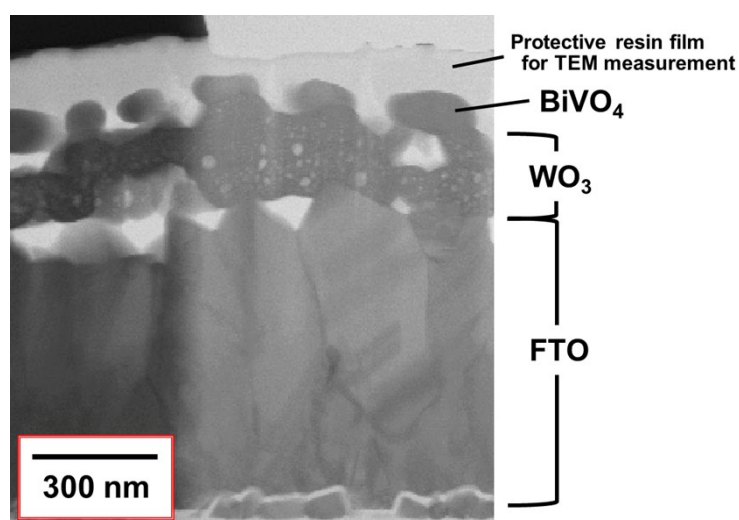


Fig. S2 Section STEM image of $\text{WO}_3/\text{BiVO}_4$ photoelectrode.

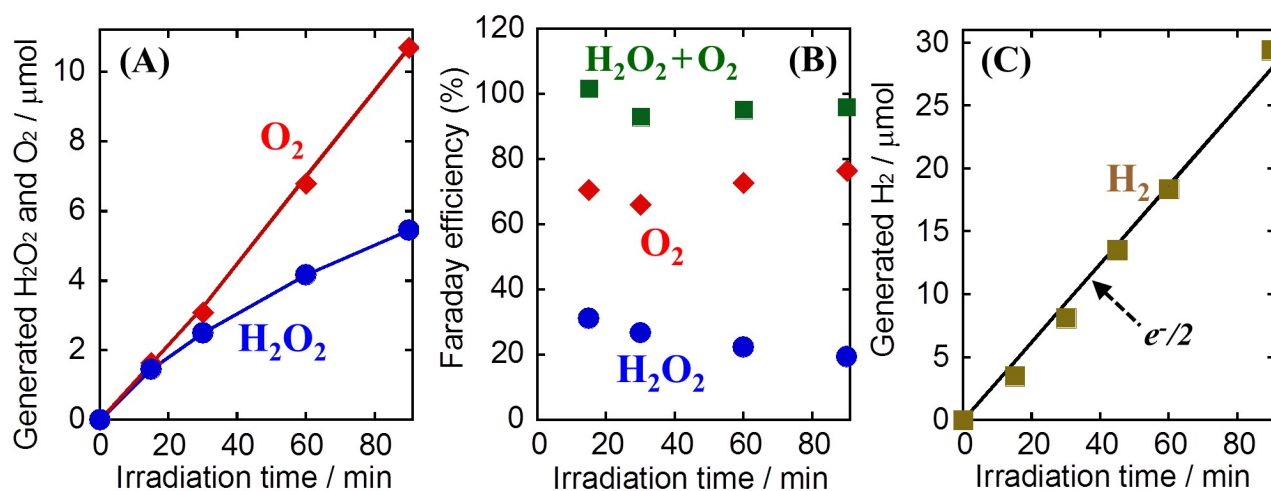


Fig. S3 Time courses of (A) the amount of H_2O_2 and O_2 generated, (B) the Faraday efficiencies of H_2O_2 and O_2 generated in the anode (oxidative) reaction, and (C) the amount of H_2 generated in the cathode (reductive) reaction in 0.5 M KHCO_3 aqueous solution (anode: 35 mL, cathode: 35 mL) using a $\text{WO}_3/\text{BiVO}_4$ photoanode under CO_2 gas (anoxic) atmosphere and simulated solar light irradiation at ambient temperature (approximately 25°C); (steady photocurrent of 1 mA at 0.4–1.2 V, photoanode size: 1.2×5.5 cm).

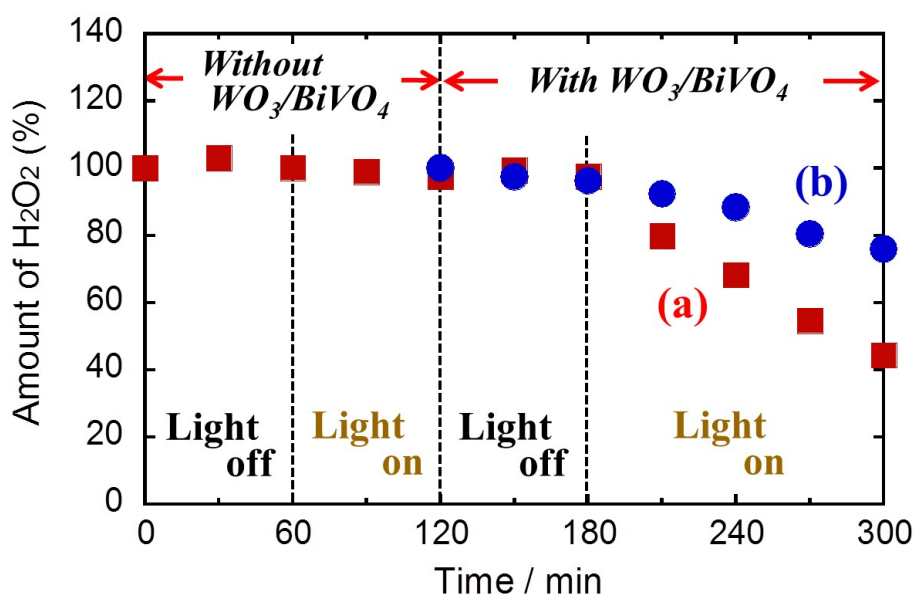


Fig. S4 Stability of H_2O_2 (550 μM) in 0.5 M KHCO_3 aqueous solution under CO_2 gas bubbling in the presence or absence of simulated solar light and a $\text{WO}_3/\text{BiVO}_4$ photoelectrode in (a) water bath (approximately 25°C) and (b) ice bath (below 5°C).

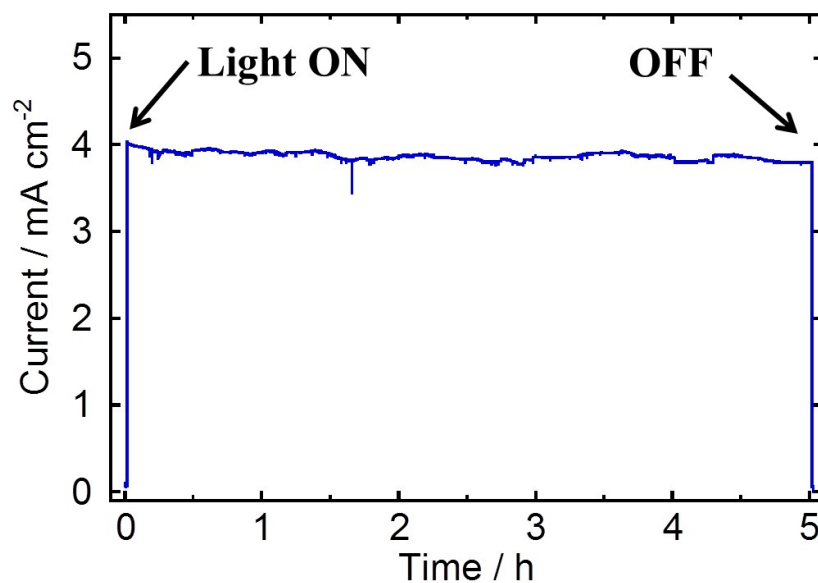


Fig. S5 *I-T* characteristic using a WO₃/BiVO₄ photoanode under CO₂ gas bubbling and simulated solar light irradiation in an ice bath in a 0.5 M KHCO₃ aqueous solution (1.2 V vs. RHE) using a two-compartment cell (irradiation area: 0.28 cm²).

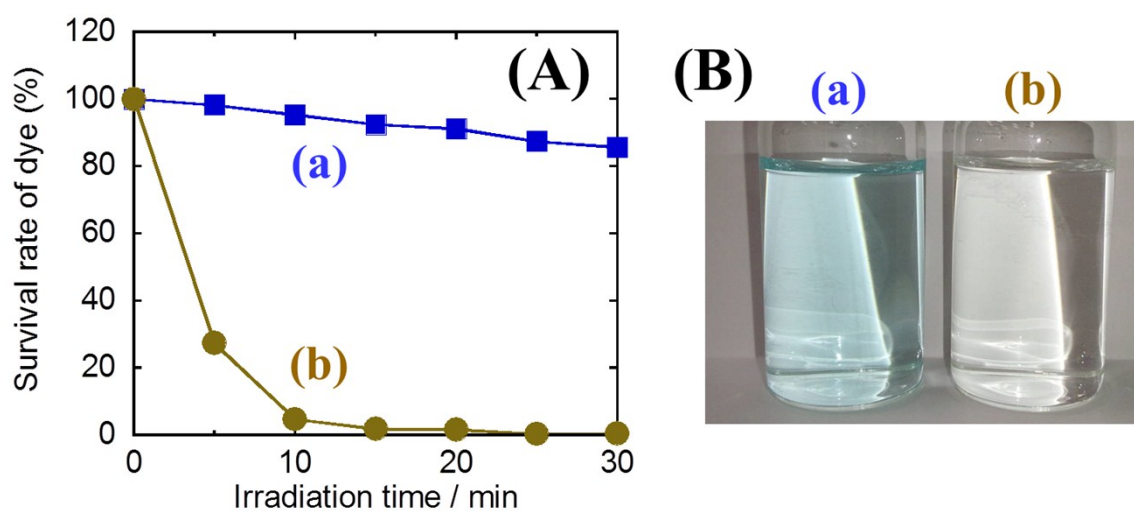


Fig. S6 (A) Time courses and (B) photographs after 30 min reaction of decolorization test of an organic methine dye (NK-3350, Hayashibara Co., Ltd.) in a 2.0 M KHCO₃ aqueous solution (a) non-containing and (b) containing *ca.* 2 mM H₂O₂ at ambient temperature.

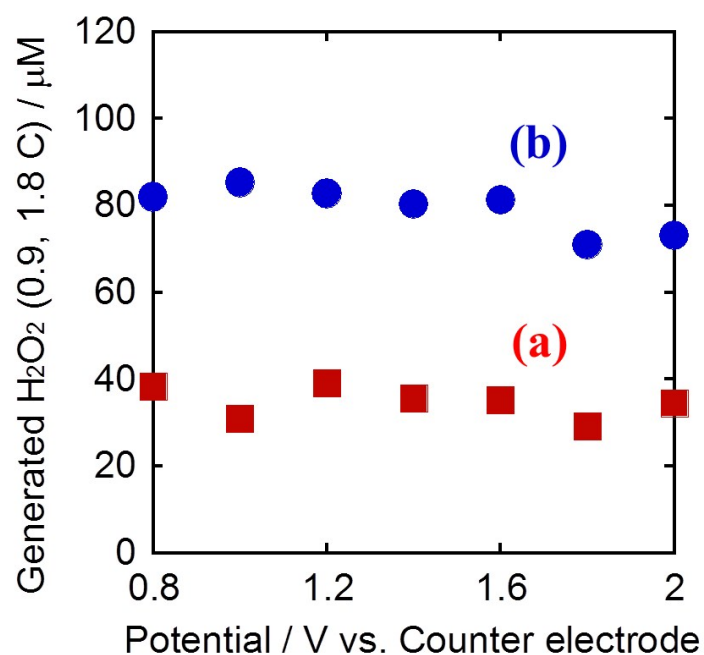


Fig. S7 Effect of the applied voltage on oxidative H₂O₂ generation in 0.5 M KHCO₃ aqueous solution (35 mL) under CO₂ gas bubbling and simulated solar light irradiation in an ice bath (below 5°C) using a WO₃/BiVO₄ photoanode; (applied electric charge: (a) 0.9 and (b) 1.8 C).

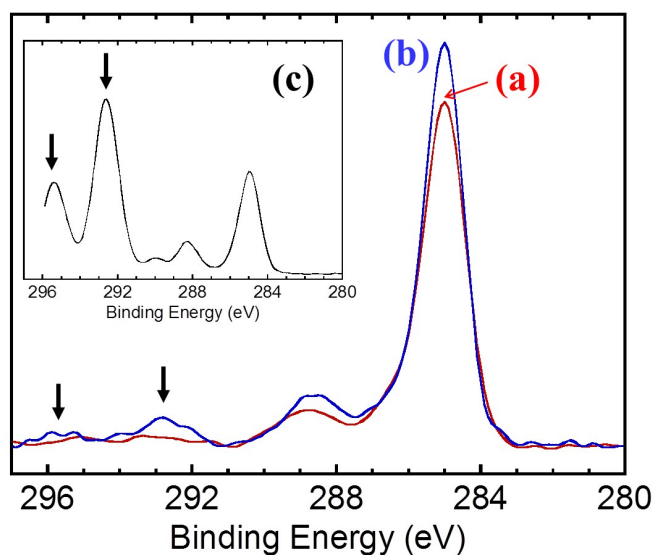


Fig. S8 XPS (C 1s) spectra of WO₃/BiVO₄ photoanode washed with deionized water (a) before and (b) after photoreaction at an applied electric charge of 7.2 C (1 mA for 120 min at 0.4–1.8 V, photoanode size: 1.2 × 5.5 cm) in a 0.5 M KHCO₃ aqueous solution, and (c) reference sample prepared by drying after a 0.5 M KHCO₃ aqueous solution was coated on the WO₃/BiVO₄ photoanode by spin coating (1000 rpm, 15 s). The binding energy was set with reference to contamination peak derived from aliphatic carbon (285.0 eV). The arrows exhibit spectra of hydrated bicarbonate derived from KHCO₃.⁸

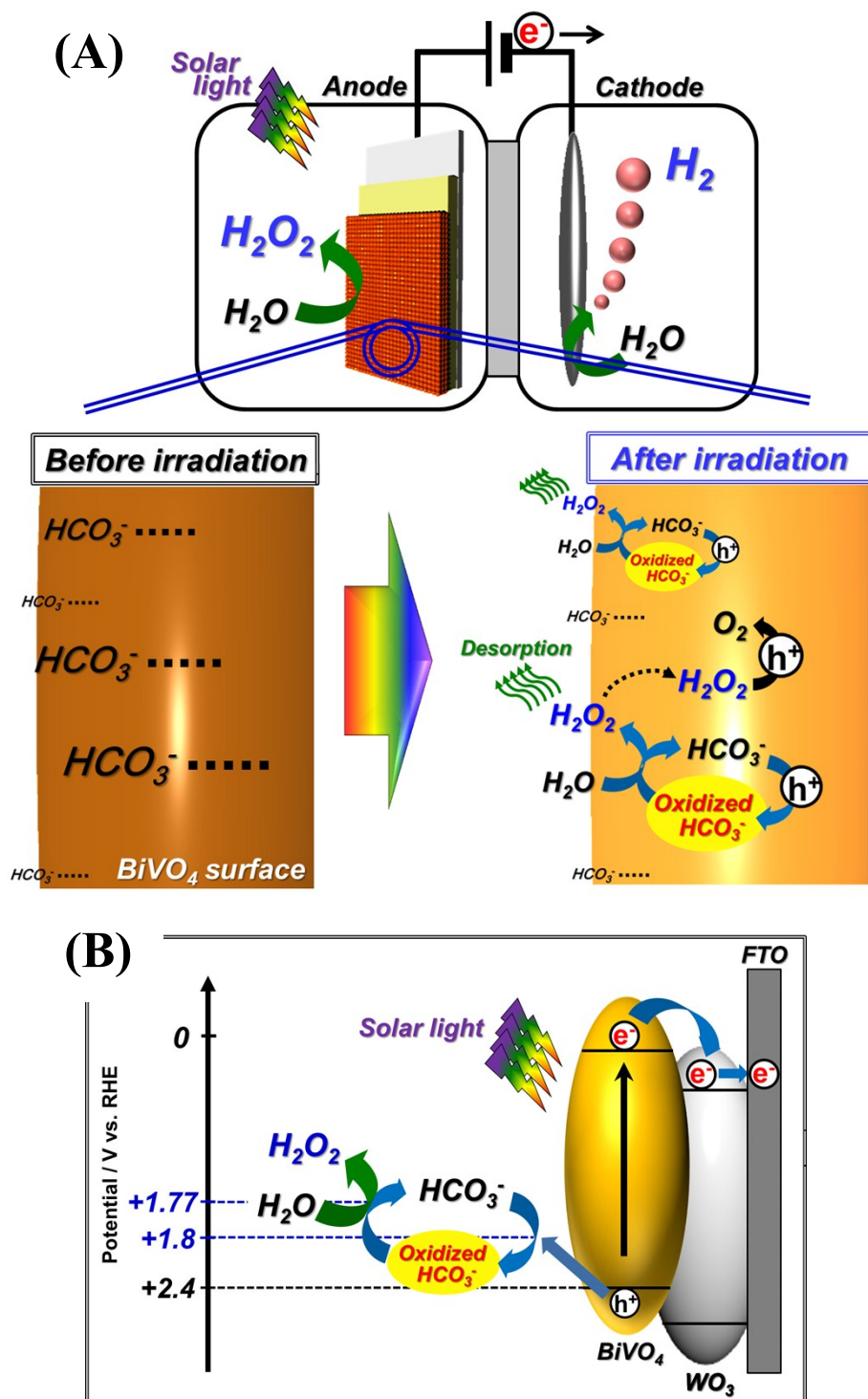


Fig. S9 Proposed (A) mechanism and (B) energy diagram on oxidative H_2O_2 generation on a $\text{WO}_3/\text{BiVO}_4$ photoanode under solar light irradiation using a KHCO_3 aqueous solution as the electrolyte.

Table S1. Comparison of XRF analysis on a WO₃/BiVO₄ photoanode before and after long-term reaction (5 h) under CO₂ gas bubbling and simulated solar light irradiation in an ice bath in a 0.5 M KHCO₃ aqueous solution (1.2 V vs. RHE) using a two-compartment cell (irradiation area: 0.28 cm²).

	/ $\mu\text{mol cm}^{-2}$				Bi/V (mole ratio)
	Bi	V	W	Sn	
Before	0.094	0.087	0.30	2.7	1.08
After	0.091	0.087	0.27	2.5	1.04

Reference

- (1) M. H. Mariano, *Anal. Chem.*, 1968, **40**, 1662.